## ☐ 디지털데일리 (Korea)

## EV Group announces NanoCleave layer release new technology... participated in Semicon Korea Show 2024– January 30, 2024

EVG introduced NanoCleave<sup>™</sup>, a revolutionary layer release technology for silicon that enables ultra-thin layer stacking for front-end processing, including advanced logic, memory and power device formation, as well as semiconductor advanced packaging. NanoCleave enables silicon wafer carriers in advanced packaging processes such as FoWLP using mold and reconstituted wafers as well as interposers for 3D SIC. At the same time, its compatibility with high-temperature processes enables completely novel process flows for 3D IC and 3D sequential integration applications − enabling hybrid and fusion bonding even of ultra-thin layers on silicon carriers, thereby revolutionizing 3D and heterogeneous integration as well as material transfer in next-generation scaled transistor designs. EVG will participate in the Semicon Korea 2024 exhibition held at COEX from the 31st to February 2nd and introduce new NanoCleave technology.

